

AMENDMENTS TO THE CLAIMS

a1

1. (currently amended) An arc chamber of an ion implanter system comprising:
an arc chamber enclosure for an electron emissive source, said source extending
into said arc chamber enclosure through a wall of said arc chamber enclosure, said wall
through which said source extends comprising an alumina insulator material surrounding
said source.

2-4. (canceled)

a2

5. (currently amended) The arc chamber of Claim 1 wherein a substantial
portion of said wall through which said source extends into the arc chamber comprises an
said alumina insulator material.